

PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Androula G. Nassiopoulou

Serial No.: 10/502,465

Filed: January 16, 2003

For: LOW POWER SILICON
THERMAL SENSORS AND
MICROFLUIDIC DEVICES BASED
ON THE USE OF POROUS SEALED
AIR CAVITY TECHNOLOGY OR
MICROCHANNEL TECHNOLOGY

Group Art Unit: To be assigned

Examiner: To be assigned

I hereby certify that this paper is being deposited with the United States Postal Service, first class postage prepaid, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

October 21, 2004

James P. Zeller Reg. No. 28,491

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450
Alexandria, VA 22313-1450
Sir:

Submitted herewith for consideration by the examiner are copies of the documents identified on the attached Form PTO-1449.

Entry and consideration of the submitted documents are solicited.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP

By

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October 21, 2004

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\*Examiner

Initials

U.S. Department of Commerce Patent and Trademark Office PTO-1449 (Modified)

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## INFORMATION DISCLOSURE STATEMENT

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ssue Date	Na	me	Class	Subclass	Filing Date if Appropriate	
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initials		Build				Yes	No
	1,251,945	05/03/00	China			Abstract only	:
	WO 98/50763	11/12/98	PCT				;

	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)
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Examiner	Date Considered	
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not		
in conformance and not considered. Include conv. of this form with next communication to applicant		